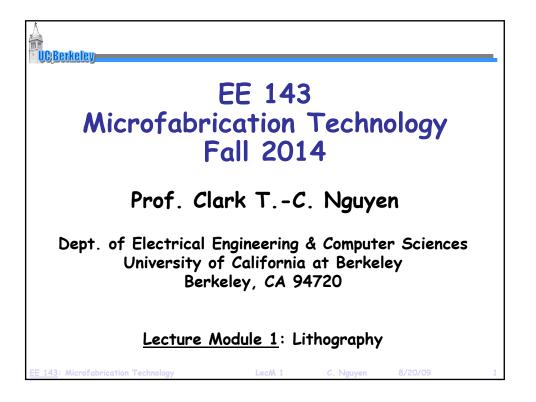
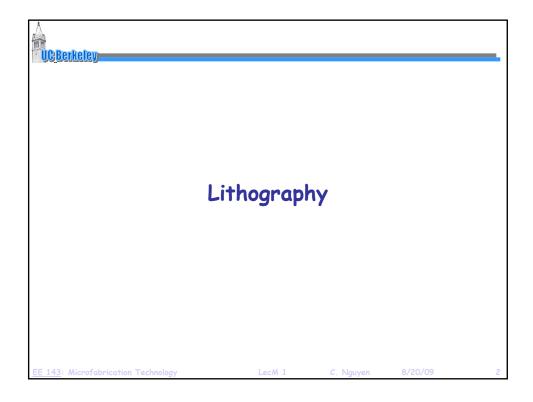
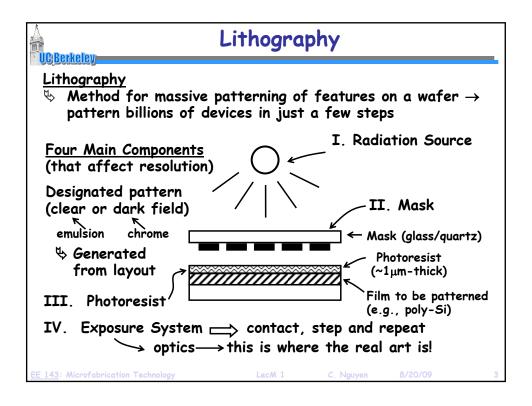
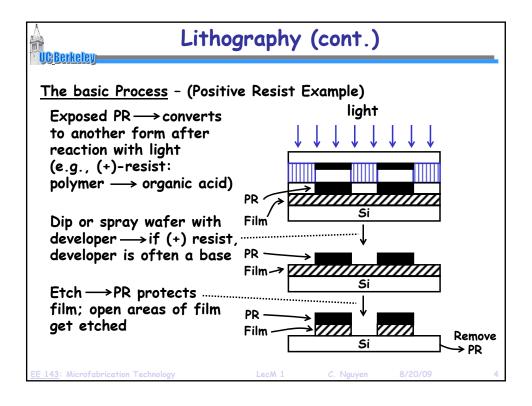
Lecture Module 1: Lithography









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Lithography (cont.)

With each masking step usually comes a film deposition, implantation and/or etch. Thus, the complexity of a process is often measured by # masks required.

NMOS: 4-6 masks Bipolar: 8-15 masks BICMOS: ~20 masks CMOS: 8-28 masks

Multi-level metallization

✓

Comb-Drive Resonator: 3 masks

GHz Disk: 4 masks

Now, take a closer look at the 4 components:

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